

Form PTO-1449				U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE		ATTY. DOCKET NO. MI22-2347	Priority SERIAL NO. 10/630,456 10/636,952	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)				APPLICANT Ying Huang et al.				
				FILING DATE 8/23/03		GROUP 2815		
U.S. PATENT DOCUMENTS								
*Examiner Initial		Document Number	Date	Name		Class	Subclass	Filing Date If Appropriate
JW	AA	5,946,601	8/99	Wong et al.				
	AB	6,033,979	3/00	Endo				
	AC	6,037,664	3/00	Zhao et al.				
	AD	6,046,104	4/00	Kepler				
	AE	6,057,417	5/00	Arnold et al.				
	AF	6,284,657 B1	09/01	Chooi et al.				
	AG	5,122,483	06/92	Sakai et al.				
	AH	6,265,779 B1	07/01	Grill et al.				
	AJ	6,410,437 B1	06/25/02	Flanner et al.				
	AJ							
	AK							
	AL							
FOREIGN PATENT DOCUMENTS								
		Document Number	Date	Country		Class	Subclass	Translation
								Yes
	AM							No
	AN							
	AO							
	AP							
	AQ							
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)								
	AR		Baliga, John, "Options for CVD of Dielectrics Include Low-k Materials," Semiconductor International June 1998, pp. 1-6					
JW	AS		Singer, Peter, "Dual-Damascene Challenges Dielectric-Etch," Semiconductor International August 1999, pp. 1-5					
	AT							
EXAMINER JOSEPH NGUYEN				DATE CONSIDERED 9/21/04				
*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.								



U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE					ATTY. DOCKET NO. M122-2347	Priority SERIAL NO. 10/030,445 10/1635952	
LIST OF ART CITED BY APPLICANT (Use several sheets if necessary)					APPLICANT Ying Huang et al.		
					FILING DATE 9/23/03	GROUP 2815	
U.S. PATENT DOCUMENTS							
Examiner Initial		Document Number	Date	Name	Class	Subclass	Filing Date If Appropriate
YN	AA	5,946,601	8/99	Wong et al			
	AB	6,033,979	1/00	Endo			
	AC	6,037,664	3/00	Zhao et al.			
	AD	6,046,104	4/00	Kepler			
	AE	6,057,417	5/00	Arnold et al.			
	AF	6,284,657 B1	09/01	Choi et al.			
	AG	5,122,483	05/92	Sakai et al.			
	AH	6,245,779 B1	07/01	Orill et al.			
	AI	6,410,437 B1	06/25/02	Pfanner et al.			
	AJ						
	AK						
	AL						
FOREIGN PATENT DOCUMENTS							
		Document Number	Date	Country	Class	Subclass	Translation
							Yes
							No
	AM						
	AN						
	AO						
	AP						
	AQ						
OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, Etc.)							
YN	AR			Baliga, John, "Options for CVD of Dielectrics Include Low-k Materials," Semiconductor International June 1998, pp. 1-4			
	AS			Singer, Peter, "Dual-Damascene Challenges Dielectric-Etch," Semiconductor International August 1999, pp. 1-5			
	AT						
EXAMINER <b>JOSEPH NGUYEN</b>				DATE CONSIDERED <b>9/21/04</b>			

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